## UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 7,132,313 B2 Page 1 of 1

APPLICATION NO. : 10/721722

DATED : November 7, 2006 INVENTOR(S) : O'Connor et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

In column 8, line 50, in Claim 10, delete "integrally forming" and insert -- chemical vapor depositing --, therefor.

In column 10, line 4, in Claim 18, after "layer." delete "adjacent to the number of transistors includes integrally forming a substantially planar diamond containing layer on a back side of the semiconductor chip.".

Signed and Sealed this

Twenty-third Day of February, 2010

David J. Kappos Director of the United States Patent and Trademark Office